## Electronic conductivity of impurity-doped Zn<sub>3</sub>N<sub>2</sub> thin films Chubu Univ. °X. Cao, K. Watarai, Y. Ninomiya, A. Sato, N. Yamada

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*INTRODUCTION*: Zn<sub>3</sub>N<sub>2</sub> is an n-type nitride semiconductor. It has a relatively wide band-gap value of 3.26~2.30 eV [1] and a small electron effective mass of ~0.3 $m_0$  ( $m_0$  denotes free electron mass). Therefore, Zn<sub>3</sub>N<sub>2</sub> is expected to be a transparent conductor with excellent conductivity. We have investigated electrical and optical properties of undoped Zn<sub>3</sub>N<sub>2</sub> polycrystalline films fabricated by sputtering. Nitrogen-deficient Zn<sub>3</sub>N<sub>2- $\delta$ </sub> films showed low resistivities ( $\rho$ ) of the order of 10<sup>-3</sup>  $\Omega$  cm [2]. To establish Zn<sub>3</sub>N<sub>2</sub> as a transparent conductor, further reduction of  $\rho$  is still needed. One way to reduce  $\rho$  is impurity-doping. Thus, we have tried impurity doping into Zn<sub>3</sub>N<sub>2</sub>. We found that oxygen is one of effective dopants to suppress  $\rho$ .

**EXPERIMENTS:** Oxygen-doped Zn<sub>3</sub>N<sub>2</sub> thin films were deposited on glass substrates heated at 200 °C by reactive RF magnetron sputtering method using a metal Zn target. Film deposition was conducted in a mixture gas of Ar, N<sub>2</sub>, and O<sub>2</sub> with various flow ratios of  $f(O_2) = O_2 / (Ar + N_2 + O_2)$  ranging from 0.0% to 0.5% at 0.1% interval. Meanwhile,  $f(N_2) = N_2 / (Ar + N_2 + O_2)$  was kept fixed at 80%.

**RESULTS & DISCUSSION**: X-ray diffraction (XRD) patterns shown in Fig. 1 indicate that all the films were phase-pure Zn<sub>3</sub>N<sub>2</sub> polycrystalline films. Fig. 2 displays  $\rho$ , carrier density ( $n_e$ ) and Hall mobility ( $\mu_H$ ) as functions of  $f(O_2)$ . The minimum  $\rho$  value of  $6.2 \times 10^{-4} \Omega$  cm was obtained at  $f(O_2)=0.2\%$ , where  $n_e$  reached the maximum value of  $1.2 \times 10^{20}$  cm<sup>-3</sup>. From these results, we inferred that oxygen acts as an effective electron donor in the Zn<sub>3</sub>N<sub>2</sub> films. As  $f(O_2)$  increased from 0.2% to 0.5%,  $\rho$  increased as a result of a reduction of  $n_e$ . The  $n_e$  reduction is probably due to the degradation of crystallinity as shown in Fig. 1. It should be noted that oxygen-doped Zn<sub>3</sub>N<sub>2</sub> films have  $\mu_H$  values larger than 60 cm<sup>2</sup> V<sup>-1</sup> s<sup>-1</sup>. These values are 1.5 times larger than those of conventional transparent conductors like Sn-doped In<sub>2</sub>O<sub>3</sub>. Therefore, oxygen-doped Zn<sub>3</sub>N<sub>2</sub> can be a high-mobility transparent conductor.



Fig.1 XRD patterns of  $Zn_3N_2$  films deposited at various  $f(O_2)$ .



Fig.2 Plots of  $\rho$ ,  $n_e$ , and  $\mu_H$  as function of  $f(O_2)$ .

## REFERENCES

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